

**POLYCYCLIC COMPOUND HAVING LACTONE STRUCTURE**

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**Abstract of JP2003113174**

**PROBLEM TO BE SOLVED:** To provide a monomer which gives a polymer suitable as a base resin of a resist material for photolithography using excimer laser as a light source.

**SOLUTION:** A polycyclic compound having a structure expressed by one out of formulae (1) to (4) (wherein, R<1> to R<7> are each independently H or an alkyl; X is a (1-8C alkyl substituted) methylene or ethylene group, or O or S; and n is 0 or a positive integer).

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